

TL/G/10034-19

DESCRIPTION

Process 16 is a non-overlay, double-diffused, silicon epitaxial device. Complement to Process 74.

APPLICATION

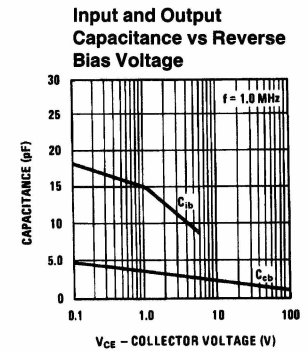
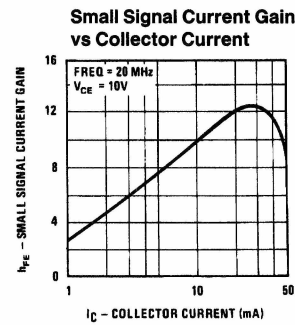
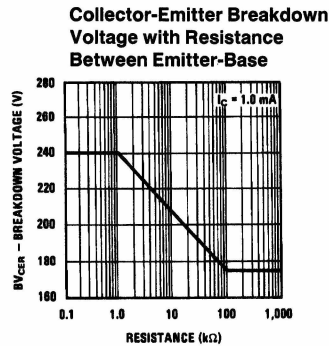
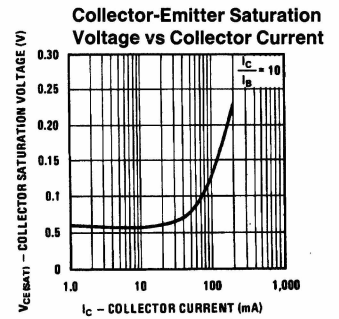
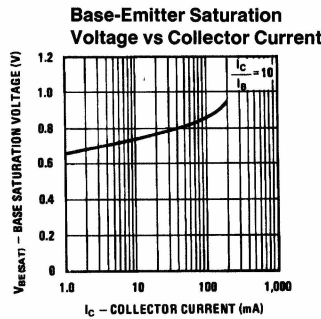
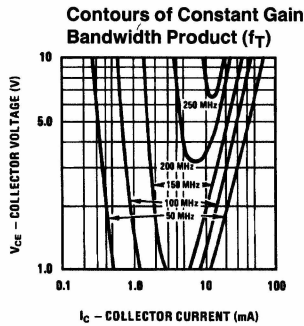
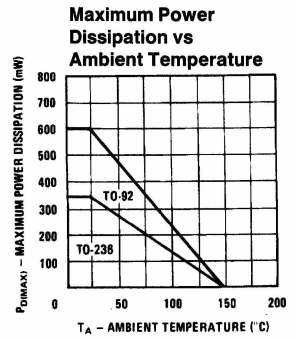
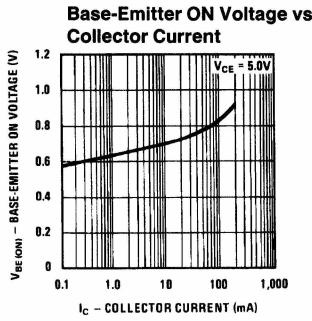
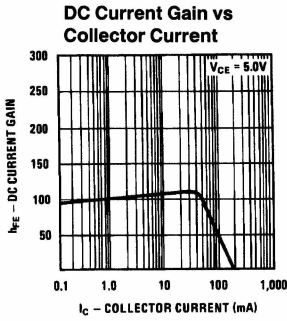
This device was designed for general purpose high voltage amplifiers and gas discharge display driving.

PRINCIPAL DEVICE TYPES
TO-92 EBC: 2N5551

TO-236: MMBT5551

ELECTRICAL CHARACTERISTICS ($T_A = 25^\circ\text{C}$)

Symbol	Conditions	Min	Typ	Max	Units
BV_{CEO}	$I_C = 1.0 \text{ mA}$	120			V
BV_{CBO}	$I_C = 10 \mu\text{A}$	140			V
BV_{EBO}	$I_E = 10 \mu\text{A}$	6			V
I_{CBO}	$V_{CB} = 100\text{V}$			100	nA
I_{EBO}	$V_{EB} = 4.0\text{V}$			100	nA
h_{FE}	$I_C = 1.0 \text{ mA}, V_{CE} = 5.0\text{V}$ $I_C = 10 \text{ mA}, V_{CE} = 5.0\text{V}$ $I_C = 50 \text{ mA}, V_{CE} = 5.0\text{V}$	40 50 20	120	300	
$V_{CE(SAT)}$	$I_C = 10 \text{ mA}, I_B = 1.0 \text{ mA}$ $I_C = 50 \text{ mA}, I_B = 5.0 \text{ mA}$			0.15 0.30	V V
$V_{BE(SAT)}$	$I_C = 10 \text{ mA}, I_B = 1.0 \text{ mA}$ $I_C = 50 \text{ mA}, I_B = 5 \text{ mA}$			0.90 1.2	V V
f_T	$I_C = 10 \text{ mA}, V_{CE} = 10\text{V}, f = 100 \text{ MHz}$	100	220		MHz
C_{ob}	$V_{CB} = 10\text{V}, f = 1 \text{ MHz}$		3.0	5.0	pF
C_{ib}	$V_{EB} = 0.5\text{V}, f = 1 \text{ MHz}$			30	pF
$P_{D(max)}$	$T_A = 25^\circ\text{C}$ $T_C = 25^\circ\text{C}$	600 350			mW mW



TL/G/10034-20